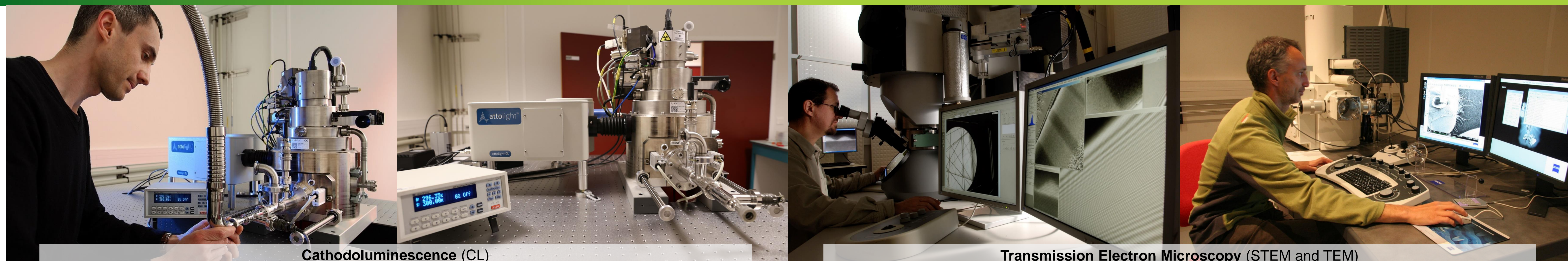


SPATIALLY CORRELATED CATHODOLUMINESCENCE AND TEM OF INGAAS QUANTUM WELL GROWN ON SILICON



Cathodoluminescence (CL)

Transmission Electron Microscopy (STEM and TEM)

Planar growth of InGaAs quantum well ¹

Sample

Blanket films

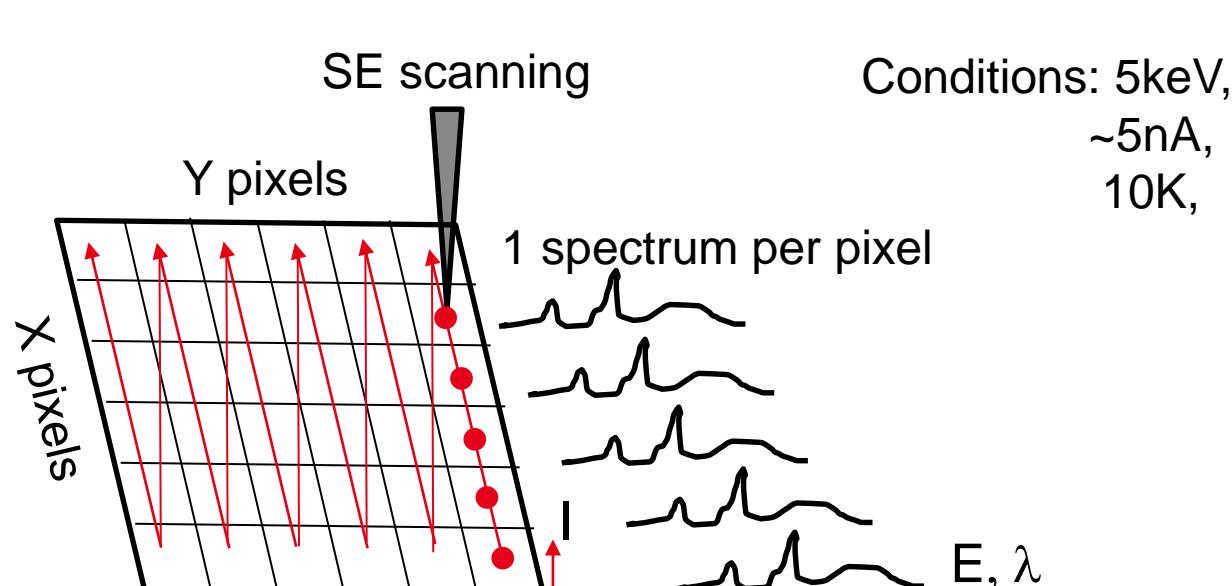
6nm InGaAs/AlAs quantum well/barrier

Applied Materials MOCVD
300mm Si (001) substrates.

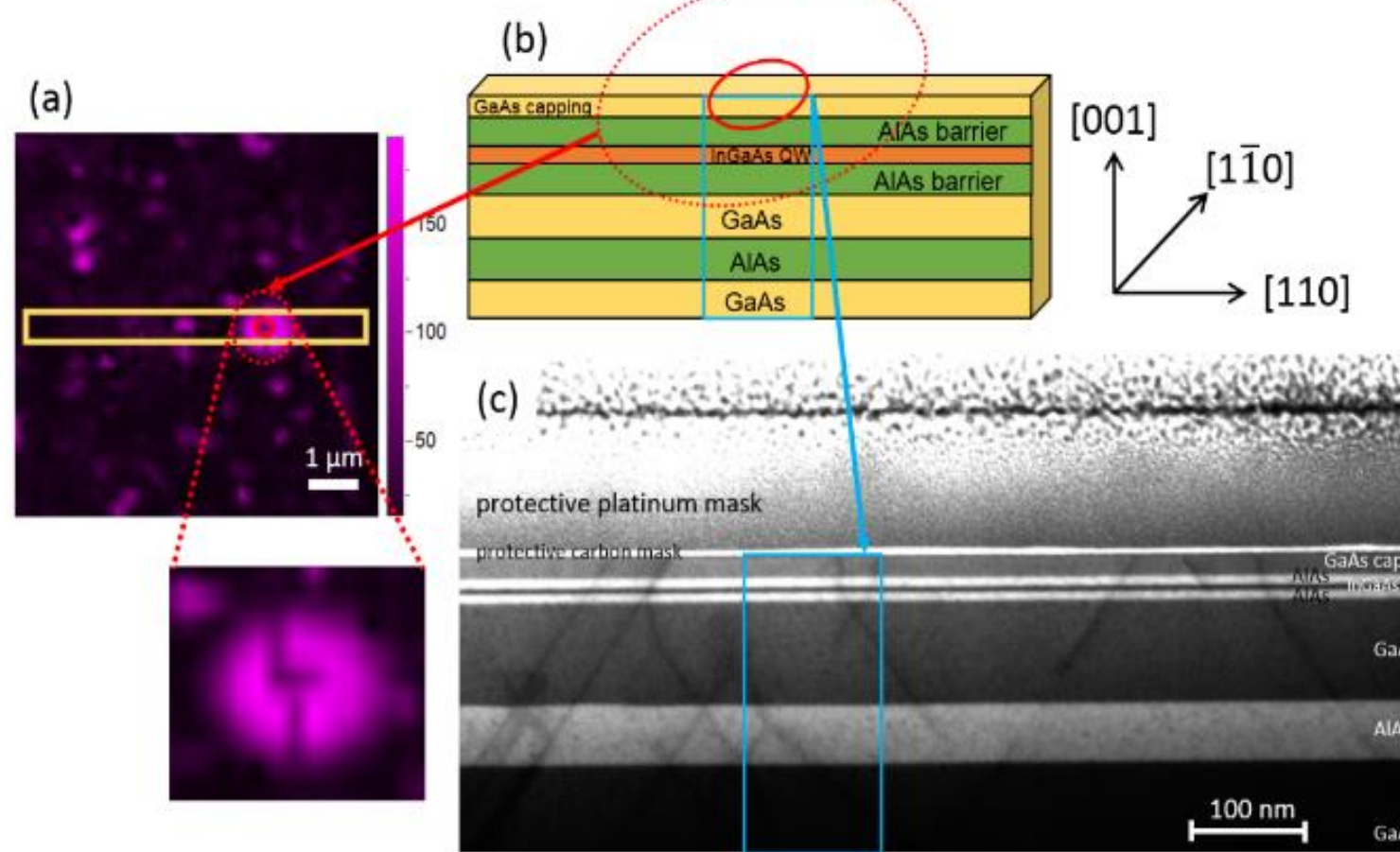
Before growth :
deoxidization in a SiConi™ chamber
with NF₃/NH₃ remote plasma + high
temperature thermal annealing under H₂
→ structure atomic steps at the surface.



CL hyperspectral mapping



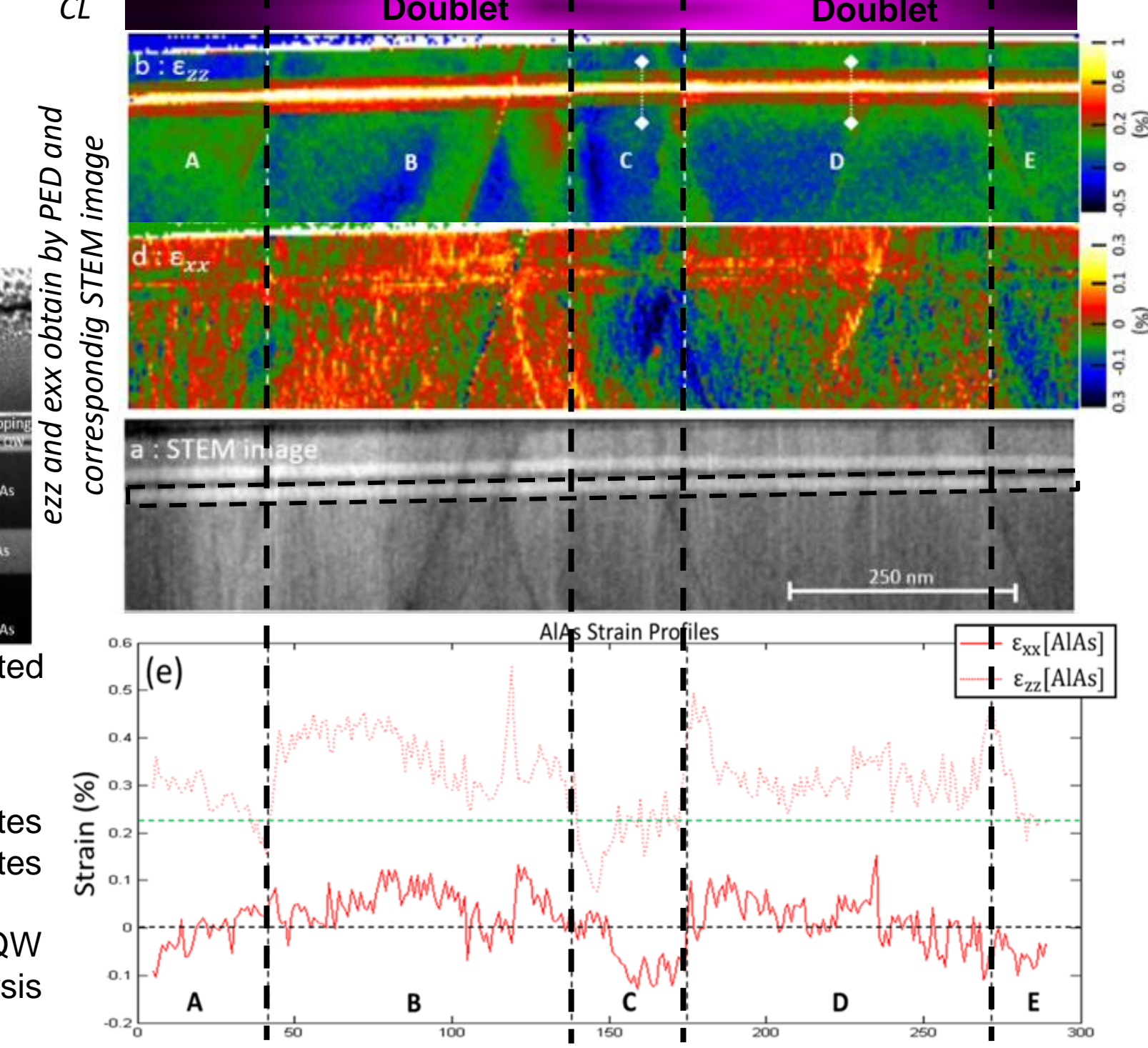
FIB Localized extraction



Extraction of a thin lamella compatible for TEM measurement located across a donut where a doublet is detected.

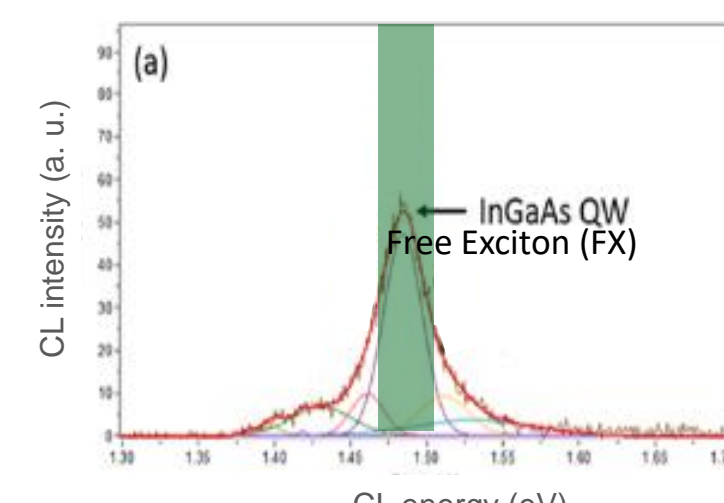
AlAs strain luminescent areas have different strain states
→ Doublet is located at different barrier strain states
Probe size to big to characterize strain inside the QW
→ Need GPA analysis

PED TEM strain characterization

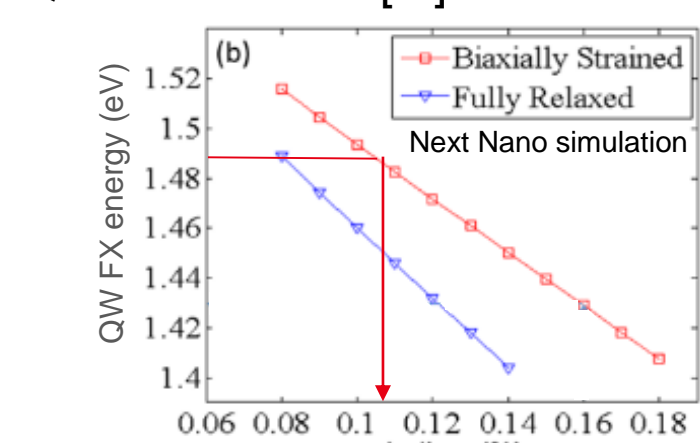


Top view CL mapping

CL QW intensity @1.49eV



Quantification of [In] in the 6nm thick QW

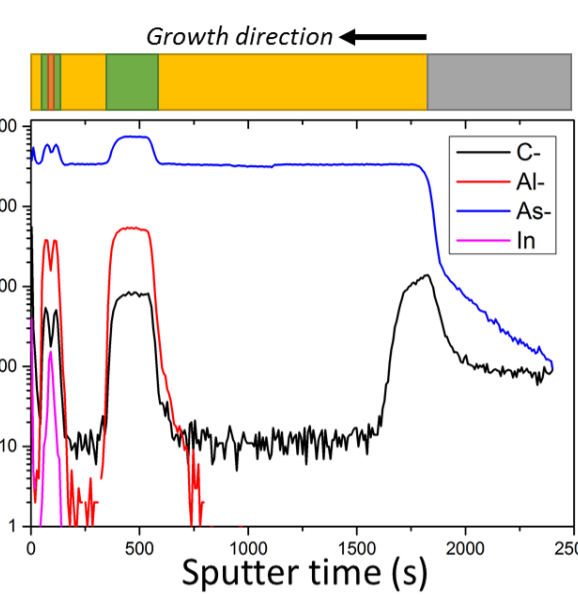


FX_{QW}=1.49eV → [In]_{nextnano}=11%
Next nano
(6nm, biaxially strained)

Detection of a thin doublet spatially localized @ 1.42eV
characterized by a donut shape, a central extinction and ΔE=9meV

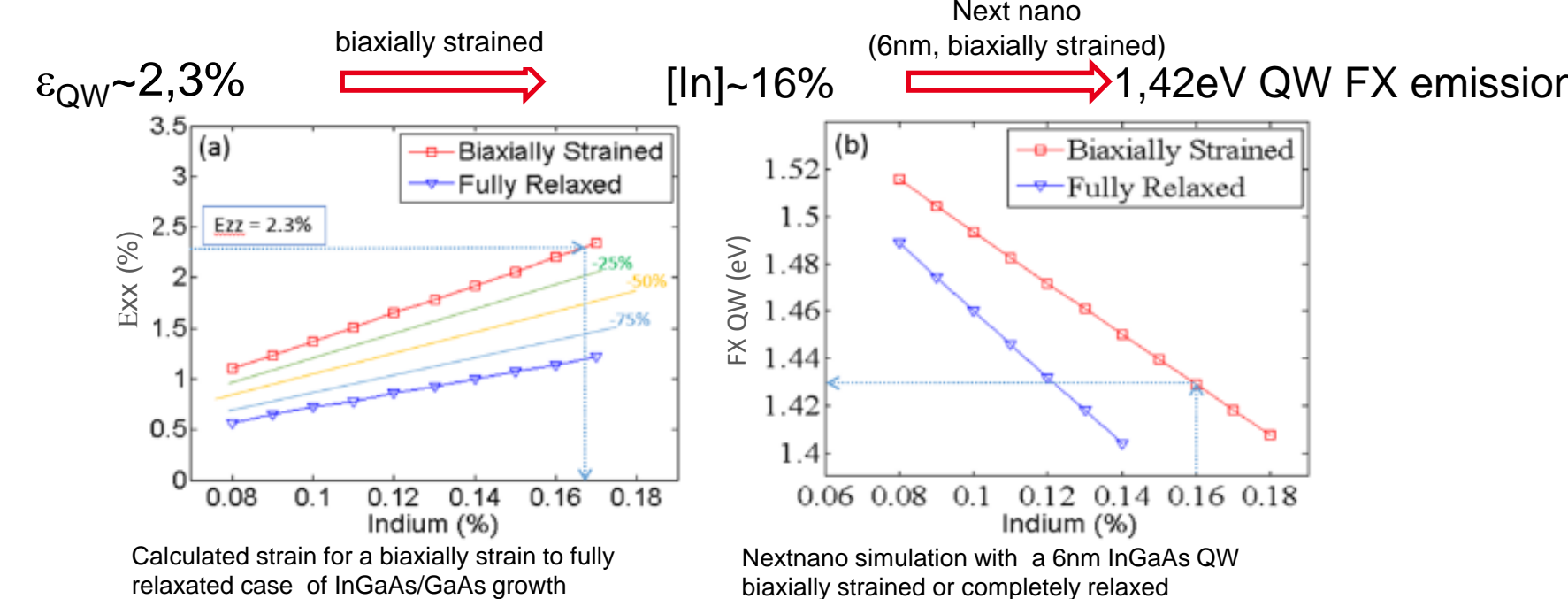
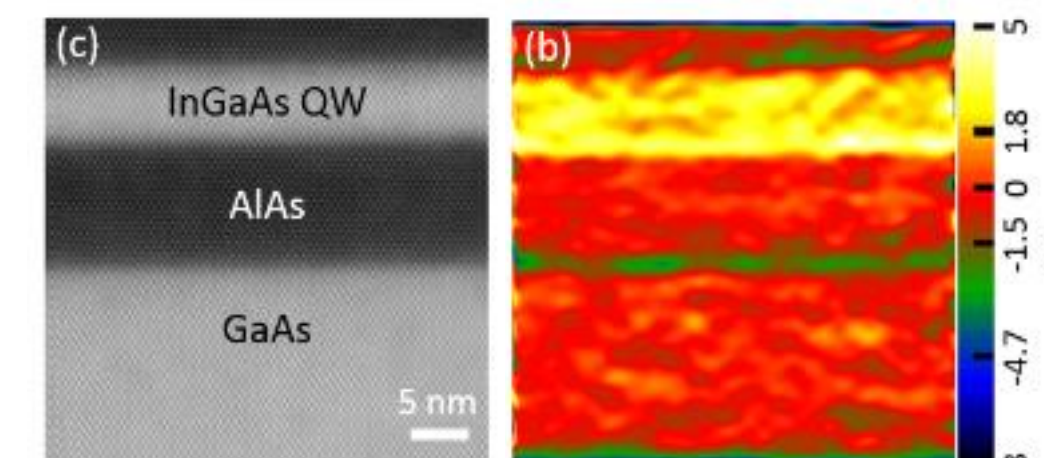
Temperature and current study of the doublet:
Saturation for high current
Quenching at low temperature (20K)
→ extrinsic defect band due to contaminant

Tof SIMS show high [C] in the barrier, only
ΔE=9meV compatible with a FX-BX doublet,
the QW exciton bounded to carbon
located outside the QW.



GPA TEM strain characterization

ϵ_{zz} obtain by GPA from corresponding HR STEM image



Nature of the doublet is elucidated as a Free exciton (FX) – Bounded exciton (BX) of the QW due to carbon located in the barrier. But the spatial shape of this emission and its FX shifted energy need local measurement of [In] and/or strain to be understood.

Spatially resolved characterization show that doublet is located in region with particular barrier strain, higher [C] in the barrier and higher [In] in the QW.
These observations are coherent with the low energy luminescent doublet circular feature observed on the sample.

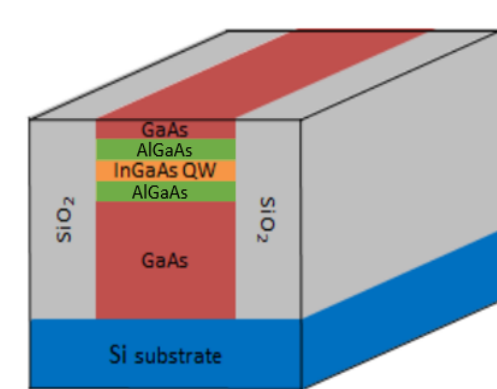
Selective epitaxy growth of InGaAs quantum well ²

Sample

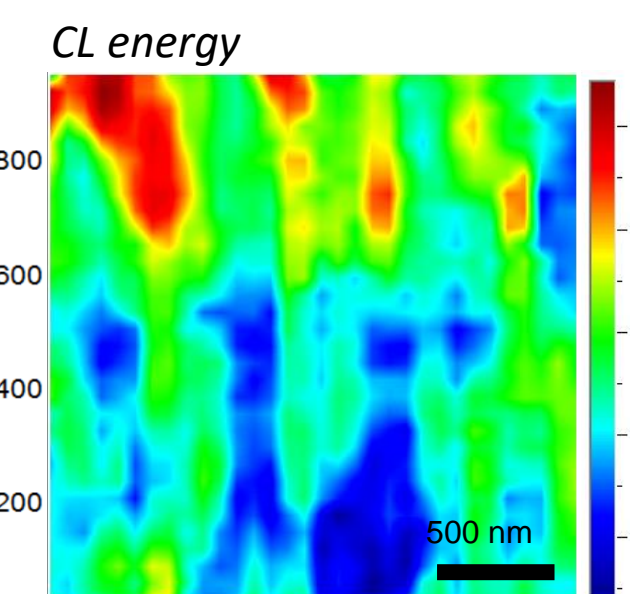
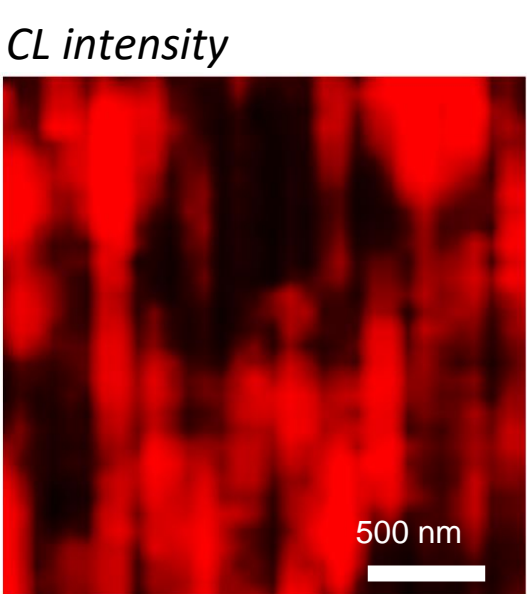
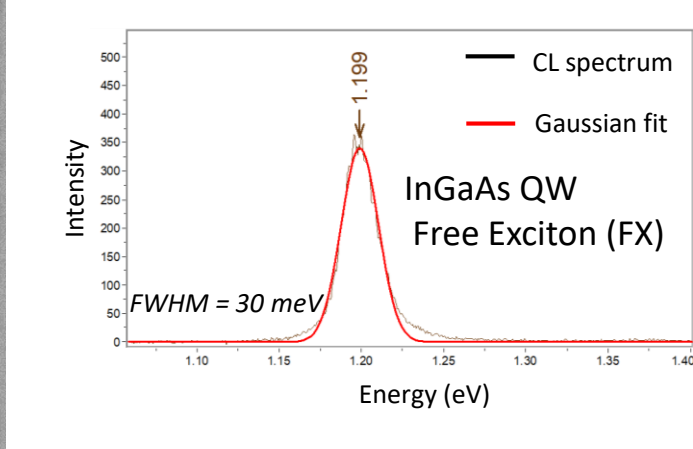
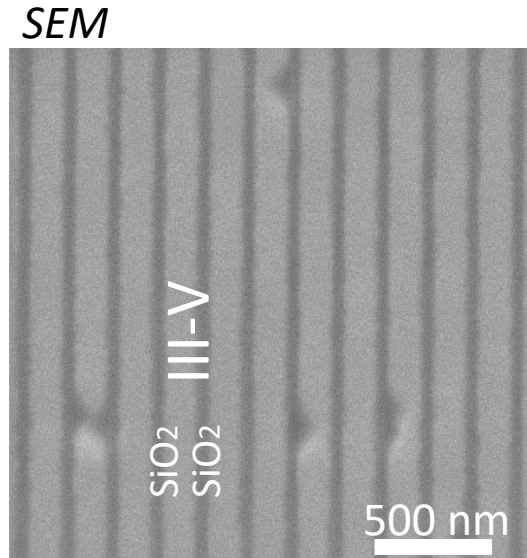
GaAs growth in SiO₂ etched pattern on Si

QW : 10nm In_{0.3}Ga_{0.7}As
Barriers : 8nm Al_{0.5}Ga_{0.5}As

Applied Materials MOCVD
300mm Si (001) substrates.

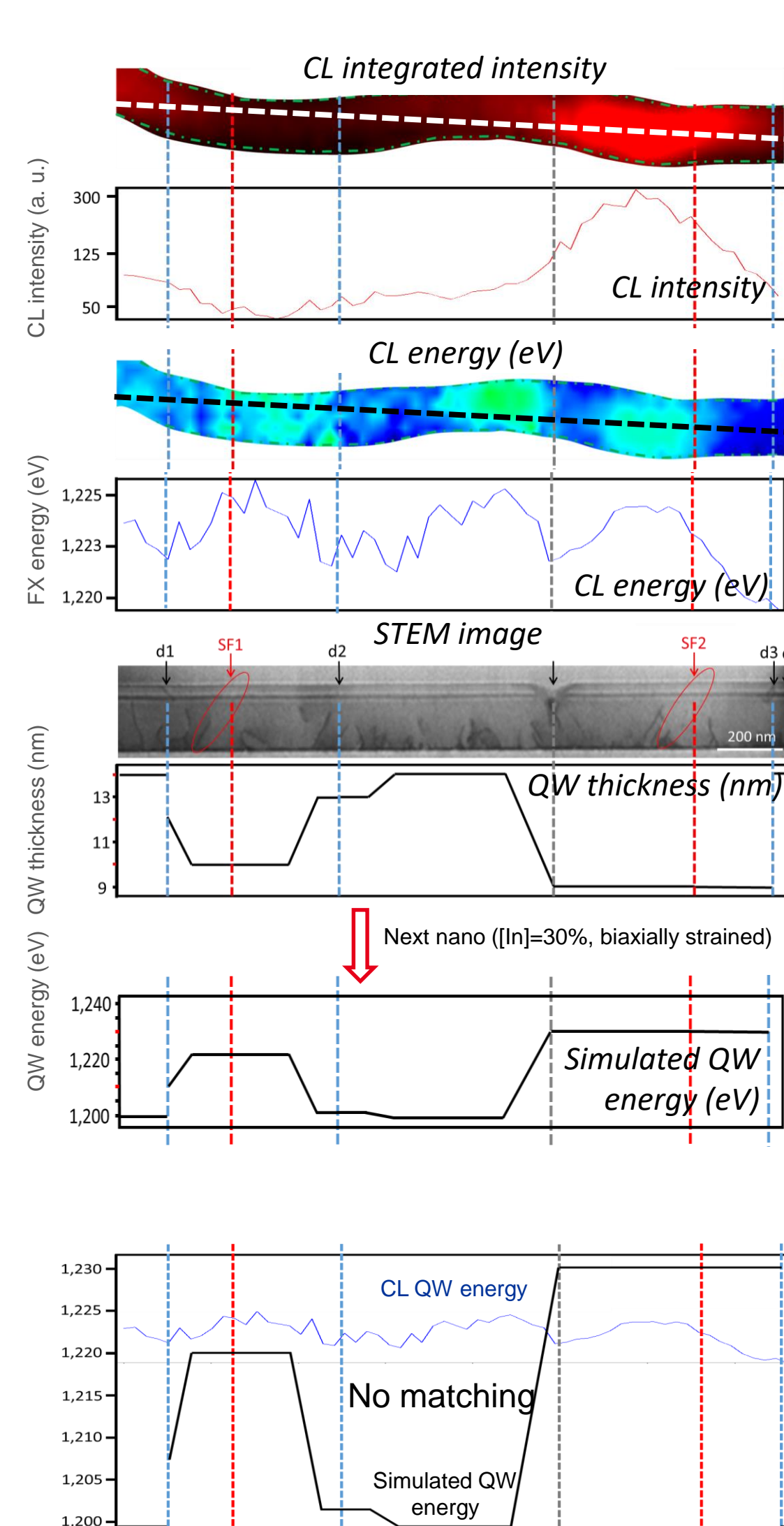


CL top view mapping

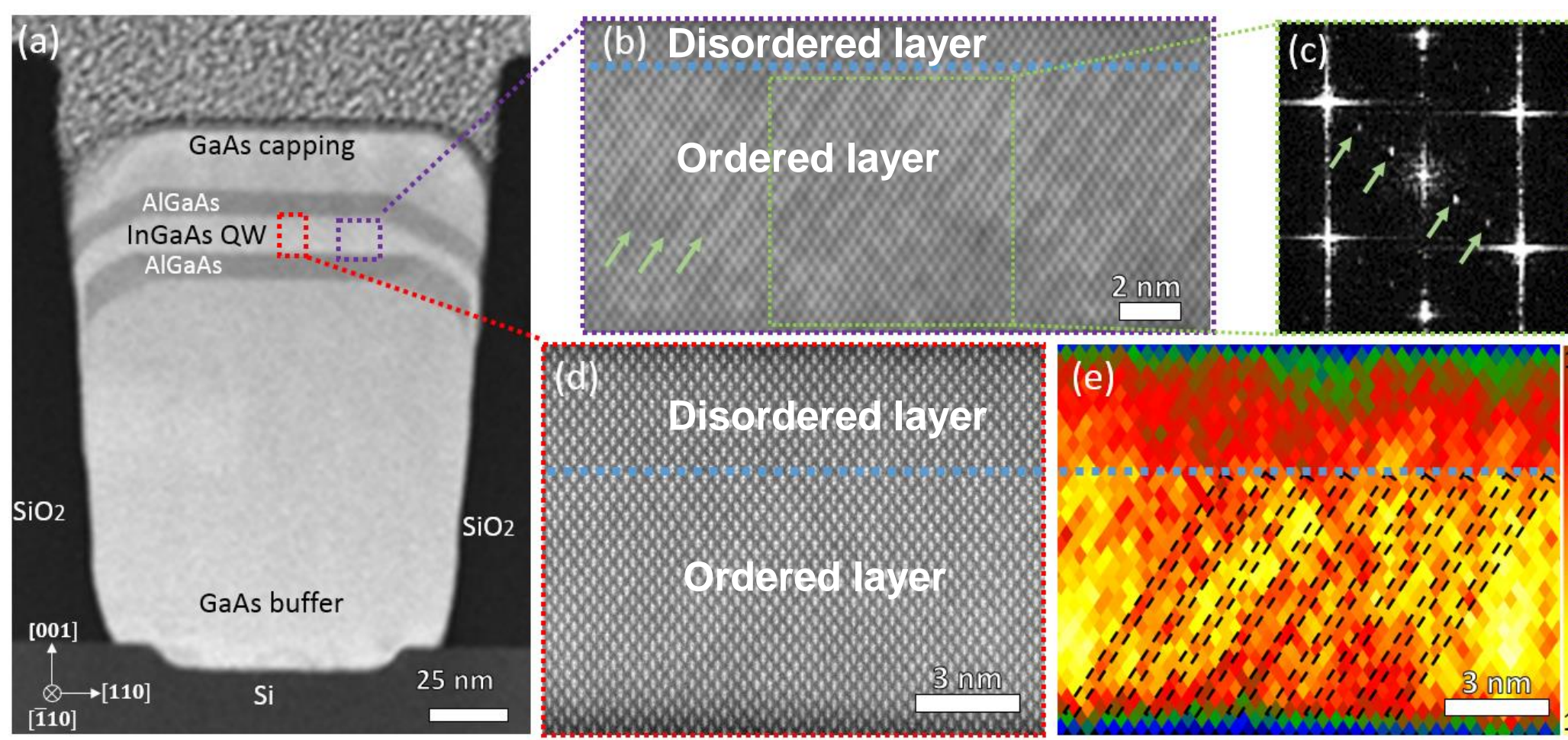


Short weak luminescent segment
@ 1.18-1.21eV
→ [In]~32%±1.5%
Very different from XRD [In]~28%

CL STEM correlation



HRSTEM & CL correlation

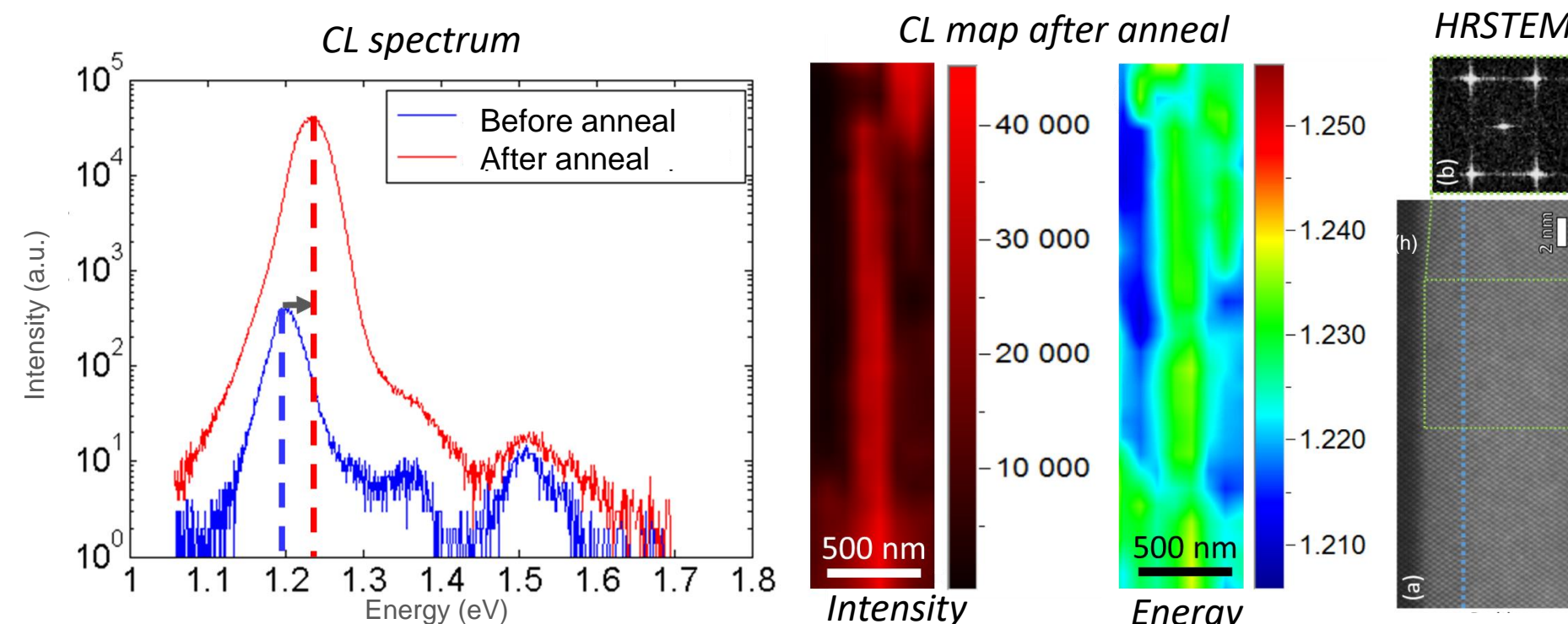


Impact of ordering on luminescence :
- imperfect crystal → low intensity
- lower bandgap energy

homogeneous top layer on luminescence → reduces radiative transition probability

Ordering is not a stable phase → 300°C anneal to remove it

Sample annealing



After anneal:
- disappearance of extra spot → no more ordering
- longer CL segment and higher CL intensity (x100)
- higher CL energy @ 1.23eV
simulation → [In]=29%±1.5%
well correlated with 28% by XRD

The 2 layers QW structure explain the mismatch between QW thickness and energy observed by CL-STEM correlation. Chemical ordering in the QW explain the low CL intensity and the discrepancy between [In] quantification from XRD and simulation of QW FX energy. Annihilation of ordering allow the full understanding of the structure.

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References

- [1] J. Roque, G. Beainy, N. Rochat, N. Bernier, S. David, J. Moeyaert, M. Martin, T. Baron, and J.L. Rouvière., *Journal of Vacuum Science & Technology B* **36**, 042901 (2018);.
- [2] J. Roque, B. Haas, S. David, N. Rochat, N. Bernier, J. L. Rouvière, B. Salem, P. Gergaud, J. Moeyaert, M. Martin, F. Bertin, and T. Baron, *Appl. Phys. Lett.* **112**, 202104 (2018).